

	Type	L #	Hits	Search Text	DBs	Time Stamp	C o m m e n t s	E r r o r s	E r r o r s
1	BRS	L3	211	(cmp or "chemical mechanical polishing") and (((secondary or tertiary) adj alcohol) or diol or triol)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/21 19:06			0
2	BRS	L4	55	3 and @pd<=20000707	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/21 17:56			0
3	BRS	L5	2	4 and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/21 17:57			0
4	BRS	L6	0	4 and 252/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/21 17:10			0
5	BRS	L7	0	4 and 510/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/21 17:14			0
6	BRS	L8	211	4not 3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/21 17:14			0
7	BRS	L9	0	4 not 3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/21 17:15			0
8	BRS	L10	156	3 not 4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/21 17:15			0

	Type	L #	Hits	Search Text	DBs	Time Stamp	C o m m e n t s	E r r o r m e s s a g e	E r r o r m e s s a g e
9	BRS	L11	2192	(cmp or "chemical mechanical polishing") and (ethylene glycol)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/21 18:54			0
10	BRS	L12	553	11 and @pd<=20000707	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/21 18:55			0
11	BRS	L13	71	12 and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/21 18:55			0
12	BRS	L14	12	12 and 438/\$.ccls. and "carboxylic acid"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/21 18:19			0
13	BRS	L15	831	(cmp or "chemical mechanical polishing") and (ethylene glycol) and (oxidiz\$)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/21 18:55			0
14	BRS	L16	113	15 and @pd<=20000707	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/21 19:12			0
15	BRS	L17	20	16 and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/21 19:12			0
16	BRS	L18	203	(cmp or "chemical mechanical polishing") and "tertiary amine"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/21 19:07			0

	Type	L #	Hits	Search Text	DBs	Time Stamp	C o m m e n t s	E r r o r s
17	BRS	L19	3	(cmp or "chemical mechanical polishing") and "tertiary amine" and (oxidiz\$4 or oxidant) and "etching agent"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/21 19:10		0
18	BRS	L22	1	21 and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/21 19:13		0
19	BRS	L21	26	20 and @pd<=20000707	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/21 19:14		0
20	BRS	L20	88	(cmp or "chemical mechanical polishing") and "tertiary amine" and (oxidiz\$4 or oxidant)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/21 19:15		0